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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/644,523	. 08/18/2003	Chien-Wei Li	Н0003938	5963	
Honeywell Inte	7590 07/11 rnational, Inc.	EXAMINER			
Law Dept. AB2			MILLER, I	MILLER, DANIEL H	
P.O. Box 2245 Morristown, NJ 07962-9806			ART UNIT	PAPER NUMBER	
			1775		
			MAIL DATE	DELIVERY MODE	
			07/11/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

## Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)	
10/644,523	LI ET AL.	
Examiner	Art Unit	
Daniel Miller	1775	

	Darmer willer	1 1773	
The MAILING DATE of this communication app	ears on the cover sheet wit	h the correspondence ad	dress
THE REPLY FILED 21 June 2007 FAILS TO PLACE THIS AF	PLICATION IN CONDITION I	FOR ALLOWANCE.	
1.  The reply was filed after a final rejection, but prior to or of this application, applicant must timely file one of the folloplaces the application in condition for allowance; (2) a N a Request for Continued Examination (RCE) in compliant time periods:	owing replies: (1) an amendm lotice of Appeal (with appeal f nce with 37 CFR 1.114. The r	ent, affidavit, or other evide ee) in compliance with 37 (	nce, which CFR 41.31; or (3)
a) The period for reply expiresmonths from the mail			
b) The period for reply expires on: (1) the mailing date of this no event, however, will the statutory period for reply expire Examiner Note: If box 1 is checked, check either box (a) o TWO MONTHS OF THE FINAL REJECTION. See MPEP	later than SIX MONTHS from the r (b). ONLY CHECK BOX (b) WH	e mailing date of the final reject	tion.
Extensions of time may be obtained under 37 CFR 1.136(a). The dathave been filed is the date for purposes of determining the period of cunder 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if checked. Any reply received by the Office lat may reduce any earned patent term adjustment. See 37 CFR 1.704(NOTICE OF APPEAL	extension and the corresponding a eshortened statutory period for re er than three months after the ma	amount of the fee. The approp	riate extension fee fice action: or (2) as
<ol> <li>The Notice of Appeal was filed on A brief in con filing the Notice of Appeal (37 CFR 41.37(a)), or any ext a Notice of Appeal has been filed, any reply must be file AMENDMENTS</li> </ol>	ension thereof (37 CFR 41.37	'(e)), to avoid dismissal of t	ths of the date of he appeal. Since
3. The proposed amendment(s) filed after a final rejection	, but prior to the date of filing	a brief, will not be entered t	pecause
(a) They raise new issues that would require further of			
(b) They raise the issue of new matter (see NOTE be	• •		
<ul><li>(c) They are not deemed to place the application in b appeal; and/or</li></ul>	etter form for appeal by mater	ially reducing or simplifying	the issues for
(d) They present additional claims without canceling a	a corresponding number of fin	ally rejected claims.	
NOTE:: (See 37 CFR 1.116 and 41.33(a)	•	•	
4. The amendments are not in compliance with 37 CFR 1.		Non-Compliant Amendment	(PTOL-324).
5. Applicant's reply has overcome the following rejection(		•	
6. Newly proposed or amended claim(s) would be non-allowable claim(s).		parate, timely filed amendm	ent canceling the
7. For purposes of appeal, the proposed amendment(s): a how the new or amended claims would be rejected is pr The status of the claim(s) is (or will be) as follows: Claim(s) allowed: Claim(s) objected to: Claim(s) rejected:		will be entered and an	explanation of
Claim(s) withdrawn from consideration:			
AFFIDAVIT OR OTHER EVIDENCE			
<ol> <li>The affidavit or other evidence filed after a final action, to because applicant failed to provide a showing of good a was not earlier presented. See 37 CFR 1.116(e).</li> </ol>	nd sufficient reasons why the	affidavit or other evidence	is necessary and
<ol> <li>The affidavit or other evidence filed after the date of filin entered because the affidavit or other evidence failed to showing a good and sufficient reasons why it is necessar</li> </ol>	overcome <u>all</u> rejections unde ary and was not earlier presen	r appeal and/or appellant fa ted. See 37 CFR 41.33(d)(	ails to provide a (1).
<ol> <li>The affidavit or other evidence is entered. An explanati REQUEST FOR RECONSIDERATION/OTHER</li> </ol>	on of the status of the claims	after entry is below or attac	hed.
<ol> <li>The request for reconsideration has been considered been see attached sheet.</li> </ol>	out does NOT place the applic	ation in condition for allowa	nce because:
12.  Note the attached Information Disclosure Statement(s)	. (PTO/SB/08) Paper No(s)		
13.			

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## Response to Arguments

The rejection stands as follows:

1. Claims 16, and 20-21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lee (US 6,733,908) in view of Stowell (US 6,207,295).

- 2. Lee teaches a Si-based substrate with a multi-layered thermal barrier coating (abstract), but is silent as to applicants claimed coating.
- 3. Stowell teaches a turbine blade wit a thermal barrier coating comprising alternating layers of SiO2 and Ta2O5 (claims 1-3 ref. and figures). The multilayer coating comprises the same material claimed by applicant in defining applicant's claimed isolation and oxygen barrier layers. The layered system of Stowell can comprise many successive layers of Silica and tantalum oxide (see figure 1), meeting claim requirements for second and third layers of isolation or oxygen barrier layers.
- 4. The multilayered coating diffuses oxygen and prevents the formation of oxides (column 3 line 15-25).
- 5. It would be obvious to one of ordinary skill in the art at the time of the invention to apply the same coating to the Si-based substrate of Lee in order to diffuse oxygen and prevents the formation of oxides which corrode the substrate. The tantalum oxide layer is deposited using CVD (column 4 line 49-60).

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6. The barrier layer, including (SiO2) layers, would be expected to inherently prevent diffusion of oxygen as claimed since it is substantially the same material taught by applicant.

7. The tantalum oxide layer is deposited using CVD (column 4 line 49-60; column 5 line 47-55).

The examiner acknowledges that the quoted section in the response to arguments was not properly cited. The examiner can't find the teaching of 1 to 500 microns in Lee.

These comments are withdrawn. However, this does not prevent a finding of obviousness or the combination of Stowell and Lee.

- 8. Applicant argued that the layers of Stowell and Lee would not be combinable because the layers of Stowell are thinner then those of Lee and are not contemplated on a more macro scale, as claimed. The examiner disagrees with applicant's arguments. Applicant points to the claimed thicknesses of the Stowell layers being 0.1-0.23 and 0.1 to 0.4 microns for the tantalum oxide and SiO2 respectively (claim 6 Stowell). However, the reference clearly teaches that the alternating layers can be 0.05 to 1.2 microns (column 4 line 5-10). The upper range of 1.2 microns overlaps applicant's claimed range. Lee teaches a range of 5 to 125 micrometers (as acknowledged by applicant remarks page 3 6/21/07); which also is in the macroscale and overlap applicant's claimed range of 1 to 100 microns.
- 9. Finally, applicant's argument s with respect to thickness of the Stowell and Lee layers being different is unconvincing. The layers of differing compositions are within the

same scale. The examiner does not see any reason why the combination and substitution of the layers in thicknesses taught by the respective references would be improper. The combination of the references providing a thickness that would overlap applicants claimed ranges.

- 10. Stowell teaches that the alternating layers can be 0.05 to 1.2 microns (column 4 line 5-10). So, the layers would be substituted as the upper layers in that thickness.

  Which would, if the upper range of 1.2 microns is chosen, overlap applicant's claimed range of thickness and composition.
- 11. Therefore, it would be obvious to one of ordinary skill in the art at the time of the invention to apply the same coating to the Si-based substrate of Lee in order to diffuse oxygen and prevents the formation of oxides which corrode the substrate. Rejection maintained.

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daniel Miller whose telephone number is (571)272-1534. The examiner can normally be reached on M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Jennifer McNeil can be reached on (571)272-1540. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

**Daniel Miller** 

JENNIFER C. MCNEIL
SUPERVISORY PATENT EXAMINER

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